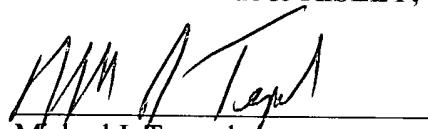


REMARKS

It is hereby respectfully requested that the Examiner enter the Amendment to the above-referenced divisional patent application. Should there be any questions or comments concerning the amendments or remarks referenced herein, the Examiner is respectfully requested to contact the undersigned attorney.

Respectfully submitted,

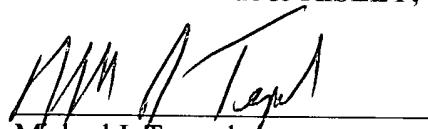
**THOMAS, KAYDEN,
HORSTEMEYER & RISLEY, L.L.P.**



Michael J. Tempel
Registration No. 41,344

Suite 1750
100 Galleria Parkway
Atlanta, GA 30339
(770) 933-9500

By:



Michael J. Tempel
Registration No. 41,344

**ANNOTATED VERSION OF MODIFIED SPECIFICATION TO SHOW CHANGES
MADE**

In The Specification

Page 1, line 6, delete "document" and substitute therefor:

--application is a division of U.S. Application Serial No. 08/932,025, entitled 'Method

And Apparatus For Low Energy Electron Enhanced Etching of Substrates in an AC or DC

Plasma Environment, filed September 17, 1997, which--.